

FORM PTO-1449	Docket Number (Optional) 81839.0107	Application Number Not assigned
<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b>	Applicant <b>JG13 Rec'd PCT/PTO 12 DEC 2001</b> Makoto IIDA et al.	
(Use several sheets if necessary)	Filing Date December 12, 2001	Group Art Unit Not assigned

**U.S. PATENT DOCUMENTS**

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

**FOREIGN PATENT DOCUMENTS**

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION (YES/NO)
M7	2001-139396	5/22/01	Japan	—	—	Yes
M7	2001-237247	8/31/01	Japan	—	—	Yes
M3	2000-344598	12/12/00	Japan	—	—	Yes
M7	2001-102385	4/13/01	Japan	—	—	Yes

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

M3	V.V. Voronkov, "THE MECHANISM OF SWIRL DEFECTS FORMATION IN SILICON", Journal of Crystal Growth 59, (1982) pp. 625-643

EXAMINER

MMA Day

DATE CONSIDERED

11/20/2002

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Docket Number (Optional)

1839.0107

Application Number

10/009,910

**INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION**

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Applicant

IIDA, et al.

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Group Art Unit

Not Assigned

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	COPY OF PAPERS ORIGINALLY FILED					

**FOREIGN PATENT DOCUMENTS**

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

MS	Aihara, et al., Extended Abstracts (The 46 <sup>th</sup> Spring Meeting, 1999); The Japan Society of Applied Physics and Related Societies, No. 1, page 469, 29a-ZB-5

EXAMINER

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